AMENDMENT

Please amend the application as indicated hereafter.

In the Claims :

1. (original) A dynamic mask module adapted to transfer a mask pattern to a photo-resist on a substrate, the dynamic mask module comprising:

a microcomputer system;

a mask pattern generator disposed over the substrate and electrically connected to the microcomputer system, wherein the microcomputer system transmits an image signal of the mask pattern to the mask pattern generator for generating pluralities of opaque areas and transparent areas and outputting the mask pattern; and

a light source disposed over the mask pattern generator, light of the light source projecting on the opaque areas and transparent areas for transferring the mask pattern to the photo-resist.

2. (original) The dynamic mask module of claim 1, further comprising a focusing lens disposed between the mask pattern generator and the substrate adapted to minify or magnify the mask pattern.

3. (original) The dynamic mask module of claim 1, wherein the mask pattern generator is a transmissive LCD or a DLP optical projector.

4.-10. (cancelled).

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